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AMENDMENTS TO THE CLAIMS

Claim 1 (Currently Amended): A multilayer thin film formed on an Si substrate by epitaxial growth, the multilayer thin film comprising:

a buffer layer formed on said Si substrate, where said buffer layer includes

an oxide thin film of zirconium or of a rare earth element on said Si substrate;

a first perovskite oxide thin film on said oxide thin film; and

an electrically conductive thin film on said first perovskite oxide thin film,

a second perovskite oxide thin film formed on said buffer layer, where said second perovskite oxide thin film comprises PbTiO<sub>3</sub> and has a (100) or (001) orientation, and

a ferroelectric thin film, which ~~is not~~ has a different composition than the second perovskite oxide thin film, ~~that~~ and which is epitaxially grown on said second perovskite oxide thin film.

Claim 2 (Previously Presented): The multilayer thin film of claim 1, wherein said second perovskite oxide thin film has insulating properties.

Claims 3-4 (Canceled)

Claim 5 (Previously Presented): The multilayer thin film of claim 1, wherein said ferroelectric thin film comprises PZT.

Claim 6 (Original): An electron device comprising a multilayer thin film as recited in claim 1.